

**AMENDMENTS TO THE CLAIMS:**

*This listing of claims will replace all prior versions, and listings, of claims in the application:*

1. (Previously presented) A liquid crystal display (LCD) comprising:

at least one thin film transistor (TFT), an interlayer insulator, and at least one reflective pixel electrode defining at least part of a pixel of the LCD and being supported by a substrate, wherein the interlayer insulator is located at least partially between the reflective pixel electrode and the substrate, and

a film comprising molybdenum nitride that is immediately below the reflective pixel electrode and in contacting the reflective pixel electrode, wherein said film comprising molybdenum nitride is also above the interlayer insulator and contacting the interlayer insulator, so that the film comprising molybdenum nitride is at least partially between the reflective pixel electrode and the interlayer insulator and contacting each of the reflective pixel electrode and the interlayer insulator so that the bottom surface of the film comprising molybdenum nitride is above the top surface of the interlayer insulator and contacting the top surface of the interlayer insulator and the top surface of the film comprising molybdenum nitride is below the reflective pixel electrode and contacting the reflective pixel electrode.

2. (Previously presented) The LCD according to claim 1, wherein the reflective pixel electrode comprises aluminum (Al).

3. (Previously presented) The LCD according to claim 1, wherein the film comprising molybdenum nitride has a nitrogen content between 5 atomic % and 30 atomic %.

4. (Previously presented) The LCD according to claim 1, wherein the interlayer insulator comprises a photosensitive resin.

5. (Previously presented) The LCD according to claim 1, wherein the interlayer insulator comprises a polymeric resin.

6. (Canceled)

7. (Previously presented) A liquid crystal display comprising:

a pair of substrates,

a liquid crystal layer between the pair of substrates,

a laminated layer provided on at least one of the substrates, wherein the laminated layer comprises an insulating film and a film comprising molybdenum nitride laminated to and over at least part of the insulating film, so that the film comprising molybdenum nitride contacts the an upper surface of the insulating film; and

a reflective metal film having a light reflecting function and provided in at least one pixel region of the display for contributing to displaying of images in the display, wherein the reflective metal film contacts the film comprising molybdenum nitride.

8. (Previously presented) The liquid crystal display according to claim 7, wherein the film comprising molybdenum nitride has a nitrogen content between 5 atomic % and 30 atomic %.

9. (Previously presented) The liquid crystal display according to claim 7, wherein the reflective metal film is a pixel electrode for applying a voltage to the liquid crystal layer.

10. (Previously presented) The liquid crystal display according to claim 7, further comprising an electrode comprising indium-tin oxide (ITO) formed on the same substrate on which the reflective metal film is formed, wherein the film comprising molybdenum nitride is provided at least partially between the reflective metal film and the electrode comprising ITO.

11. (Previously presented) A liquid crystal display (LCD) comprising:  
at least one thin film transistor (TFT),  
an insulating layer at least partially provided over the TFT;  
at least one reflective pixel electrode defining at least part of a pixel of the LCD; and  
a film comprising molybdenum nitride in direct contact with the under-side of said reflective pixel electrode, such that the molybdenum nitride of said film comprising molybdenum nitride is in direct contact with both (a) the under-side of the reflective pixel electrode and (b) the upper surface of the insulating layer.

12-14. (Canceled)

15. (Previously presented) The LCD of claim 1, wherein the pixel electrode is in electrical communication with a drain electrode of the TFT through a contact hole defined in the interlayer insulator, and wherein the reflective pixel electrode is above the film comprising

molybdenum nitride and contacting the film comprising molybdenum nitride at least in areas not in said contact hole.

16. (Previously presented) The display of claim 7, wherein the reflective metal film is in electrical communication with a drain electrode of a TFT through a contact hole defined in the insulating film, and wherein the reflective metal film is above the film comprising molybdenum nitride and contacting the film comprising molybdenum nitride at least in areas not in said contact hole.

17. (Currently amended) The LCD of claim ~~[[12]]~~ 11, wherein the pixel electrode is in electrical communication with a drain electrode of the TFT through a contact hole defined in the insulating layer, and wherein the pixel electrode is above the film comprising molybdenum nitride and contacting the film comprising molybdenum nitride at least in areas not in said contact hole.